

Figure. 1 Schematic cross-section view of formation Ta films **1110** on silicon substrate **1100** without buffer (Figure 1(a)) and with buffer layer **1120** (Figure 1(b)).(Narayan)

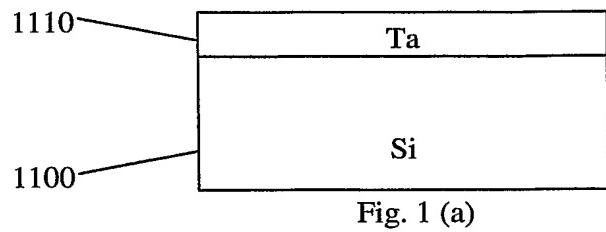


Fig. 1 (a)

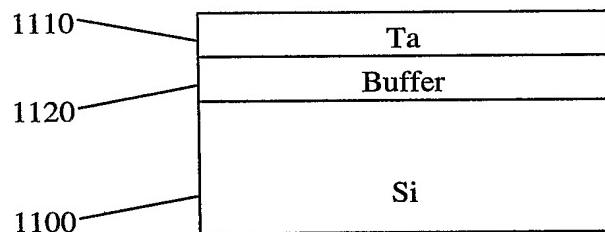


Fig. 1 (b)

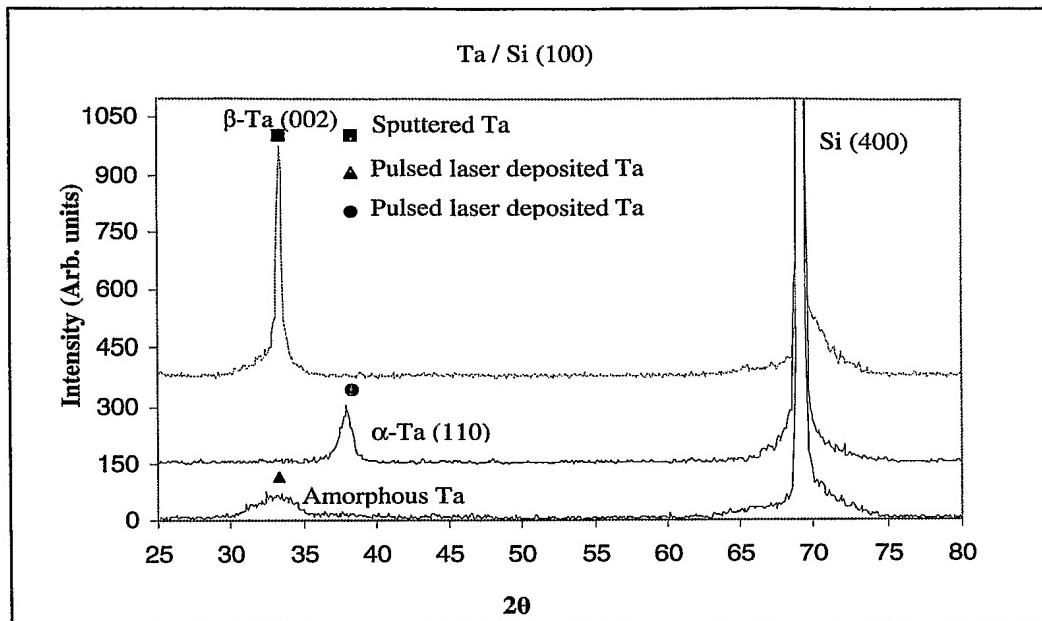
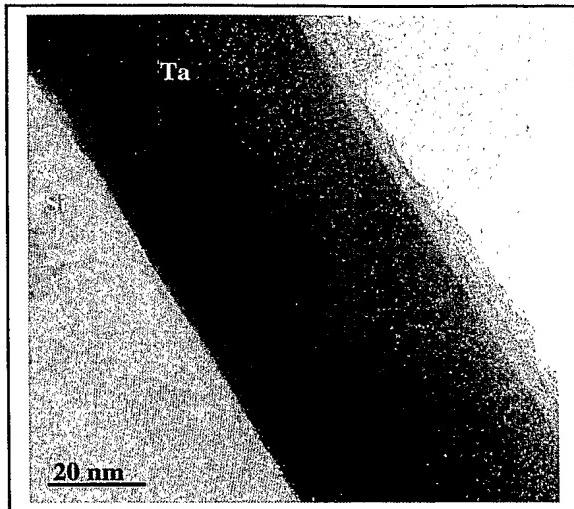
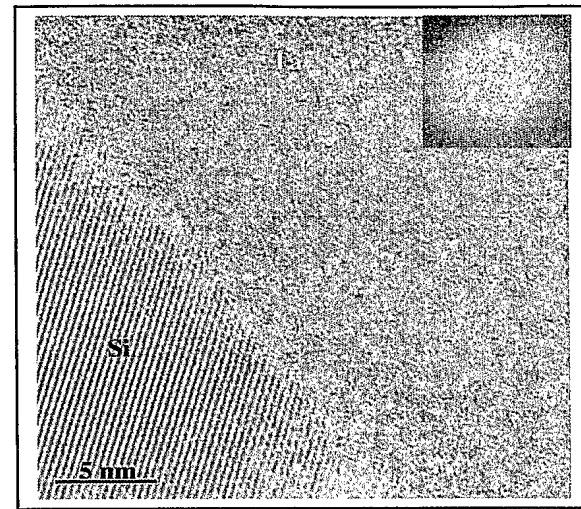


Fig. 2. Narayan



(a)



(b)

Fig. 3.Narayan.

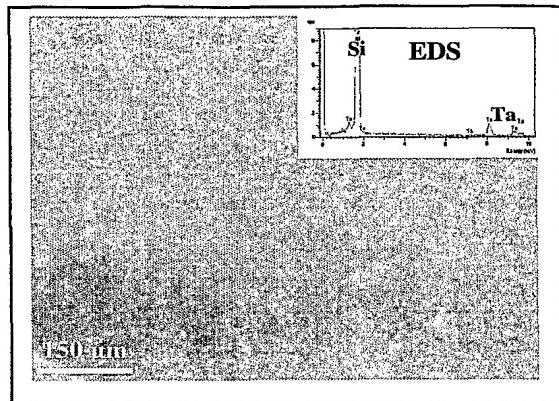


Fig. 4. Narayan

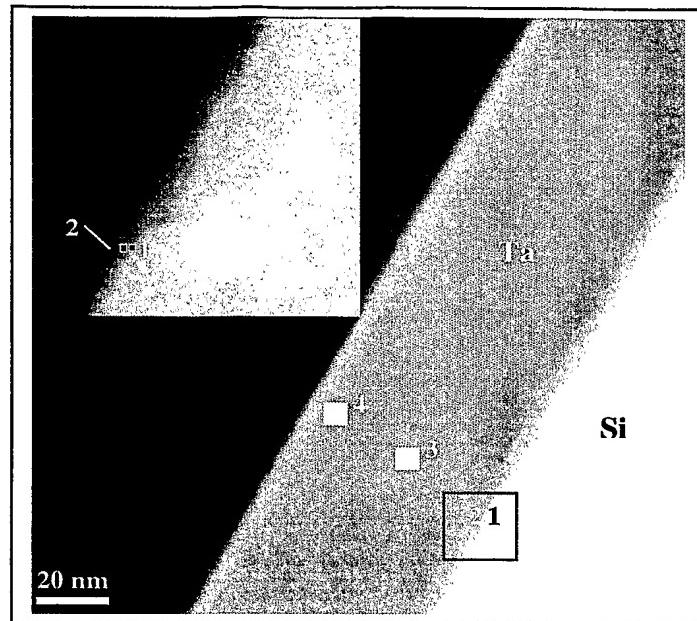


Fig. 5. (a) Narayan

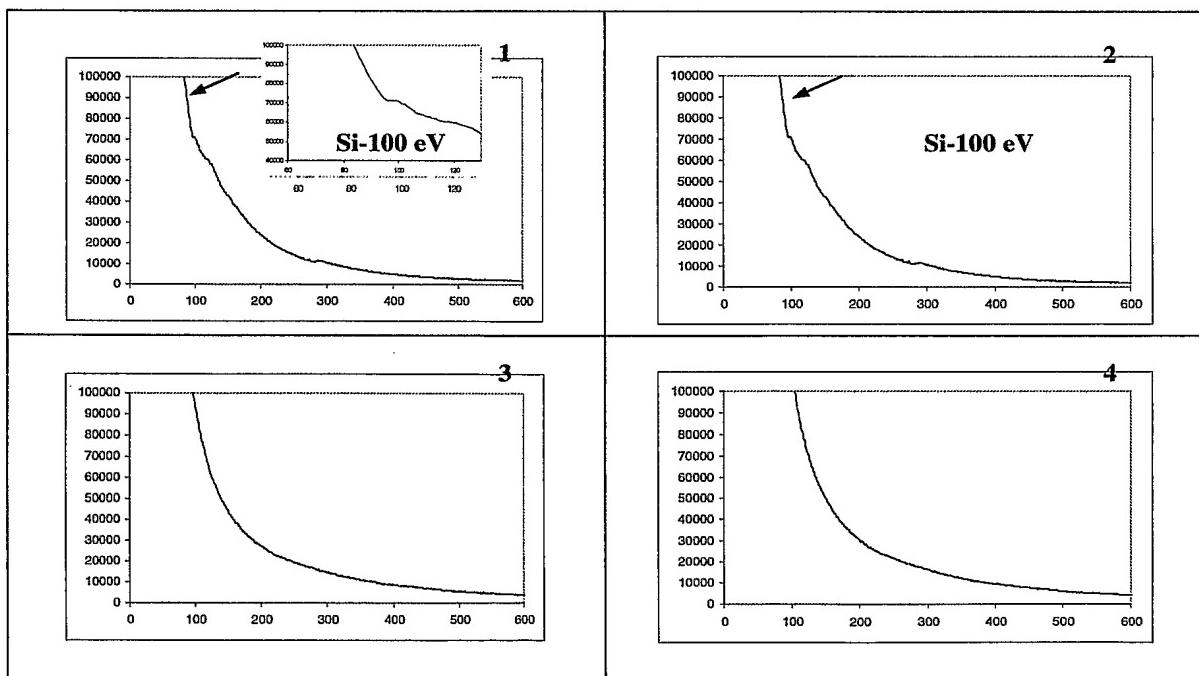


Fig. 5 (b) Narayan

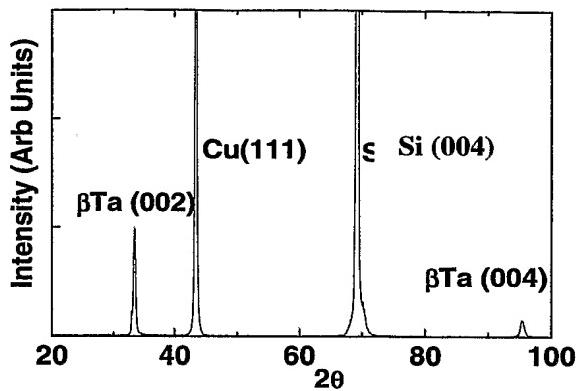


Fig. 6. (a) Narayan

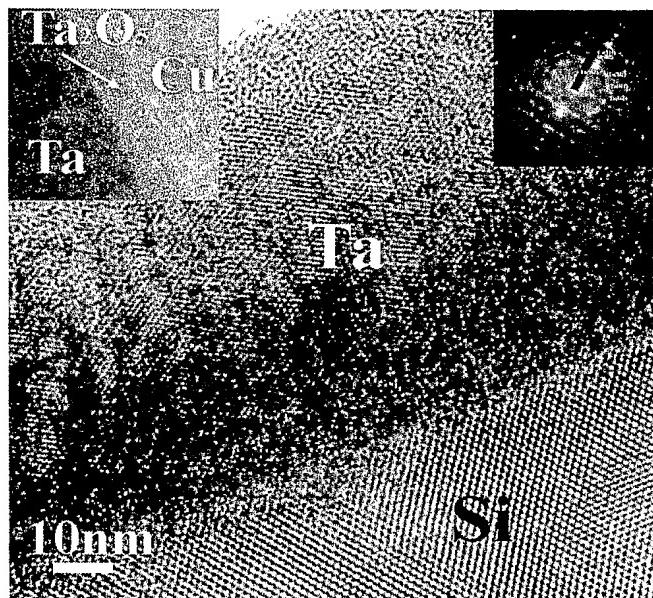


Fig. 6. (b) Narayan

Figure 7(a) Narayan

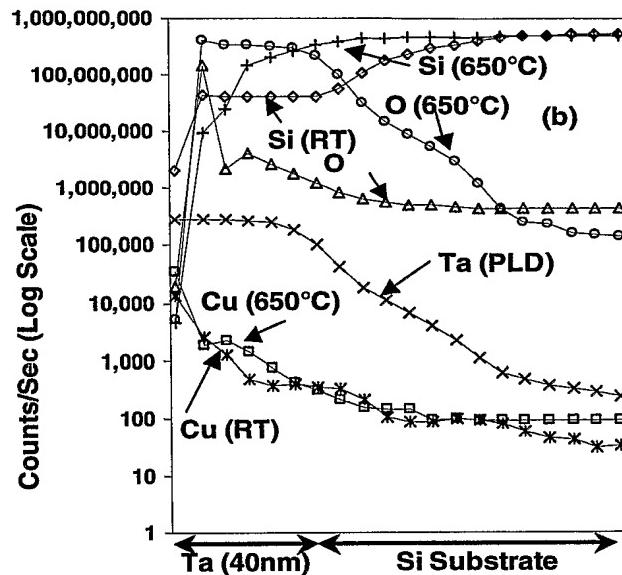
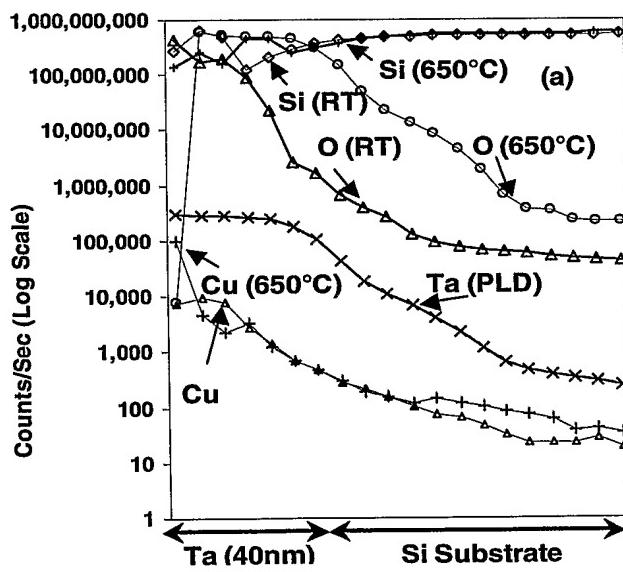


Figure 7(b) Narayan



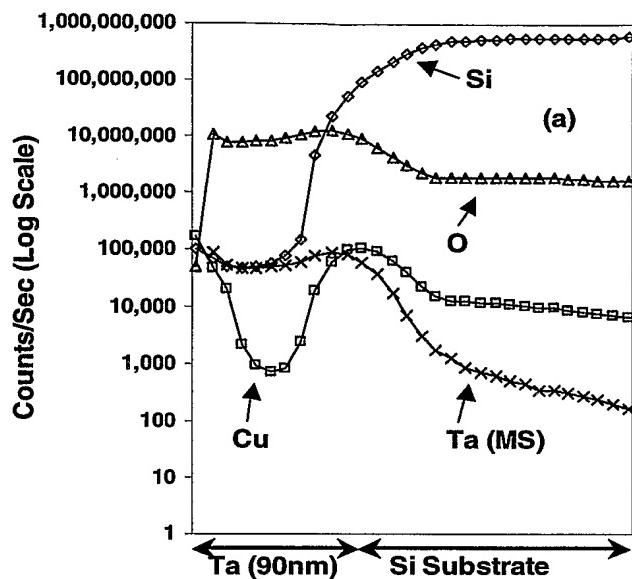


Fig. 8. (a) Narayan

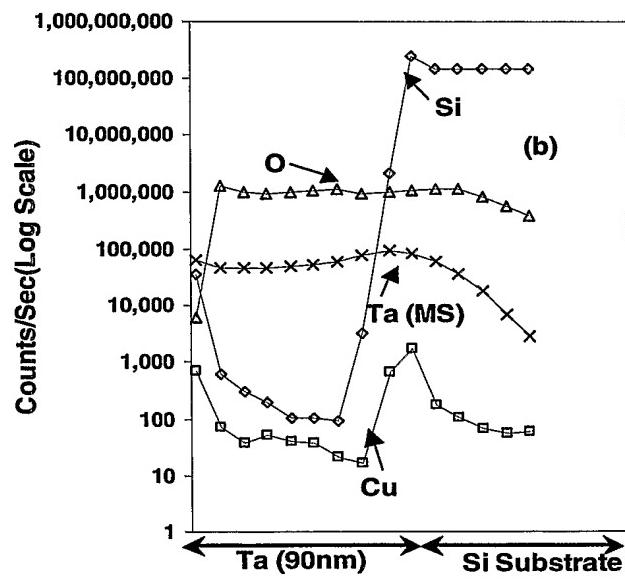


Fig. 8. (b) Narayan

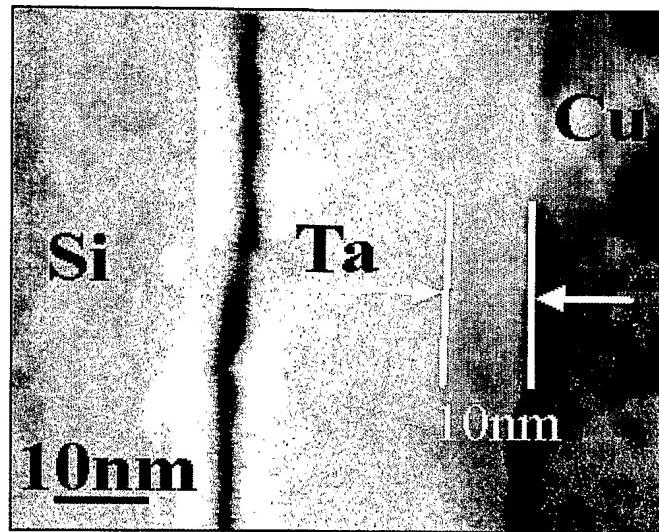


Fig. 9(a). Narayan

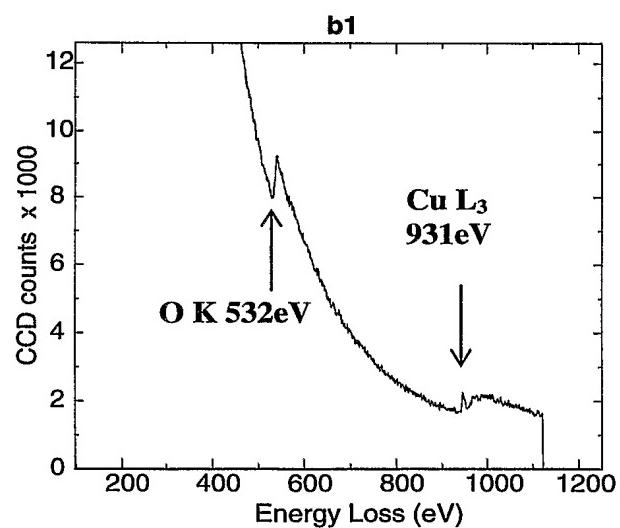


Fig. 9. (b) Narayan

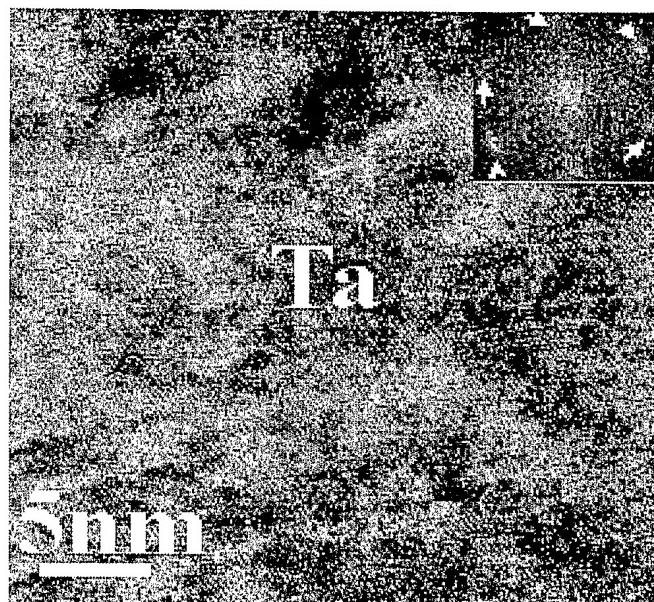


Fig. 10. Narayan

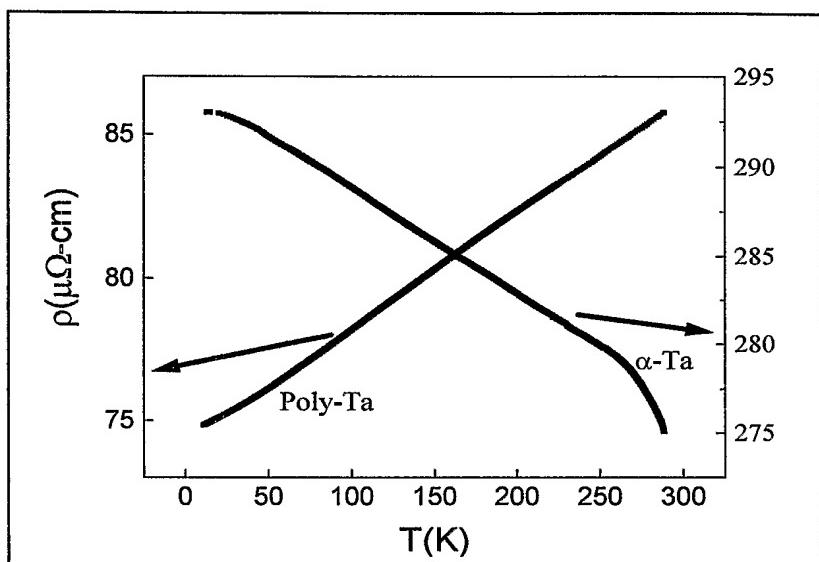


Fig. 11. Narayan

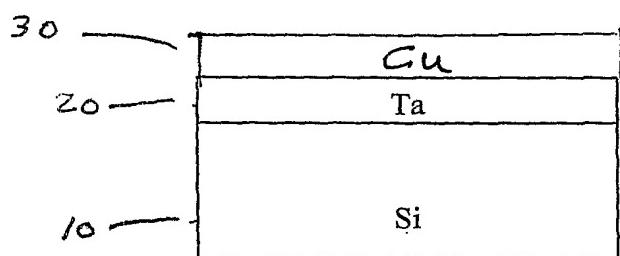


Fig. 12 (a)

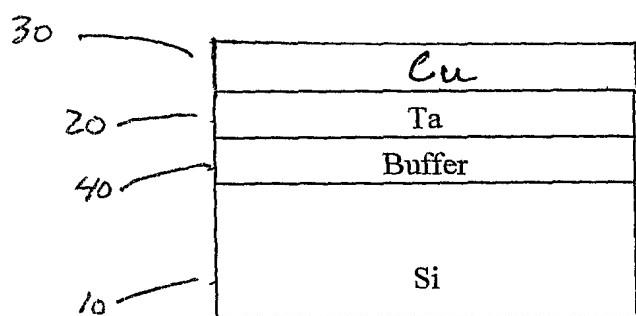


Fig. 12 (b)

Figure. 1 Schematic cross-section view of formation Ta films **1110** on silicon substrate **1100** without buffer (Figure 1(a)) and with buffer layer **1120** (Figure 1(b)).(Narayan)

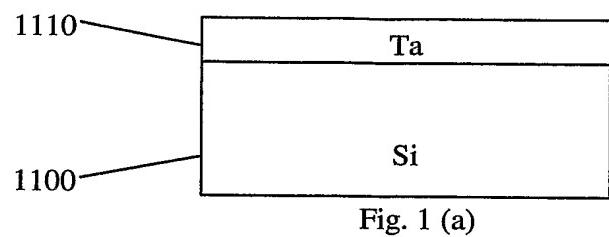


Fig. 1 (a)

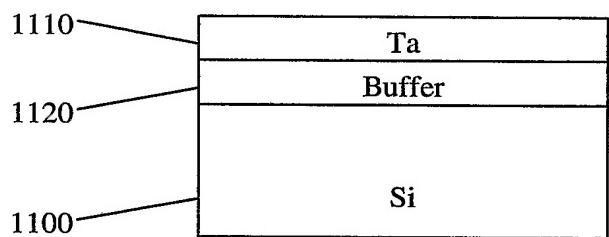


Fig. 1 (b)